

02/12/2008



Docket No.: SON-2769  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Hidetoshi Ohnuma

Application No.: 10/603,689

Confirmation No.: 2872

Filed: June 26, 2003

Art Unit: 1756

For: EXPOSURE METHOD, MASK  
FABRICATION METHOD, FABRICATION  
METHOD OF SEMICONDUCTOR DEVICE  
AND EXPOSURE APPARATUS

Examiner: D. C. Davis

**AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. 1.116**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated July 11, 2007, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 15 of this paper.